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| LIST OF PATENTS AND PUBLICATIONS APPLICANT'S INFORMATION DISCLOSURE STATEMENT (Form PTO-1449) | Attorney Docket: 101769-311- WCG | Serial No. TBA (371 of PCT/EP07/00555) 107533831 |
| | Applicants: Marc HUSEMANN, et al. | |
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EXAMINER: /Anish Desai/**DATE CONSIDERED:**

02/04/2008

- **EXAMINER:** Initial if Reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformation and not considered, include copy of this form with next communication to applicant.
- ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. 7A.D.

- *1 Equivalent to US 6,479,608
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